

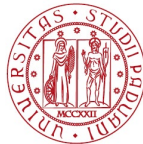
Ion Beam Analysis for Materials Characterization

G. Maggioni

➤ Laboratory of Materials Physics for Nuclear Physics at INFN-LNL (MatLab-LNL)



➤ University of Padua



UNIVERSITÀ
DEGLI STUDI
DI PADOVA

Personnel involved

- Dr. G. Maggioni
- Dr. S. M. Carturan
- Dr. W. Raniero
- Dr. S. Bertoldo
- Dr. C. Carraro
- Prof. D. De Salvador
- Dr. F. Sgarbossa
- Dr. V. Rigato
- Dr. M. Campostrini

MatLab-LNL

- Since 1992
- Radiation detectors: gamma detectors and plastic scintillators
- Nuclear targets

Activity at the AN2000 accelerator

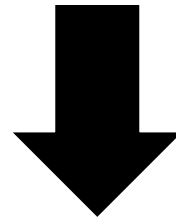
Materials characterization in the frame of R&D projects

Analytical techniques

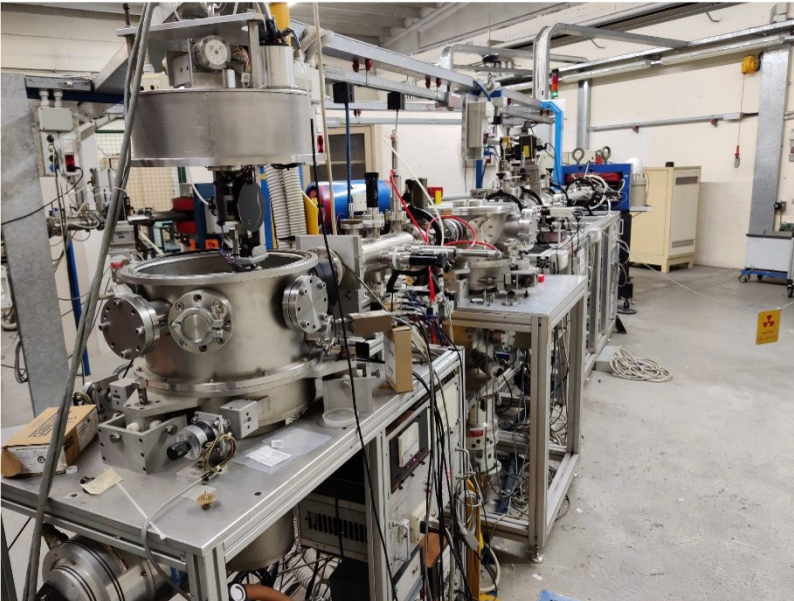
- Rutherford Backscattering Spectrometry (RBS, ^4He up to 2 MeV)
- Channelling RBS (^4He up to 2 MeV)
- Elastic Recoil Detection Analysis (ERDA ^4He 1.6 MeV)
- Nuclear Reaction Analysis (NRA ^1H 1.6 MeV, 660 keV,)



Analysis Chamber



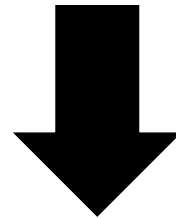
- Elemental composition: qualitative and quantitative
- Contamination
- Film thickness (down to a monolayer)
- Hydrogen measurement
- Materials structure



AN2000 - 60° Beam Line

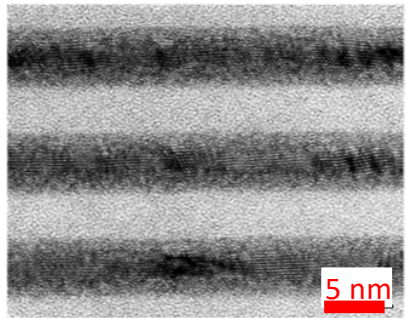
Analytical techniques

- Rutherford Backscattering Spectrometry (RBS, ^4He up to 2 MeV)
- Channelling RBS (^4He up to 2 MeV)
- Elastic Recoil Detection Analysis (ERDA ^4He 1.6 MeV)
- Nuclear Reaction Analysis (NRA ^1H 1.6 MeV, 660 keV,)



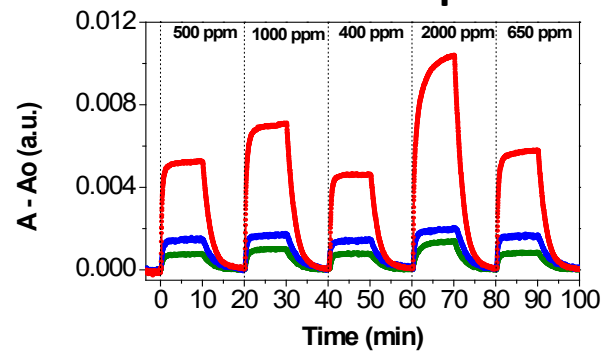
Past R&D Activities

Multilayer Technology

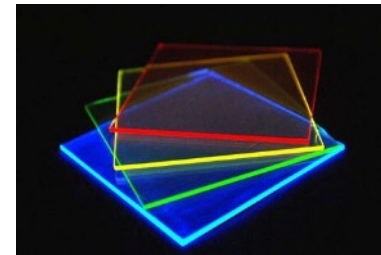


EUV Multilayer Mirrors

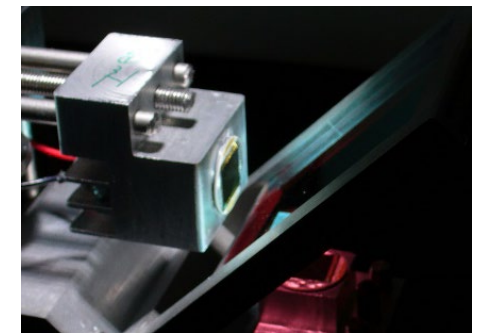
Methanol vapour



Optical gas/VOC sensors



Luminescent Solar Concentrators



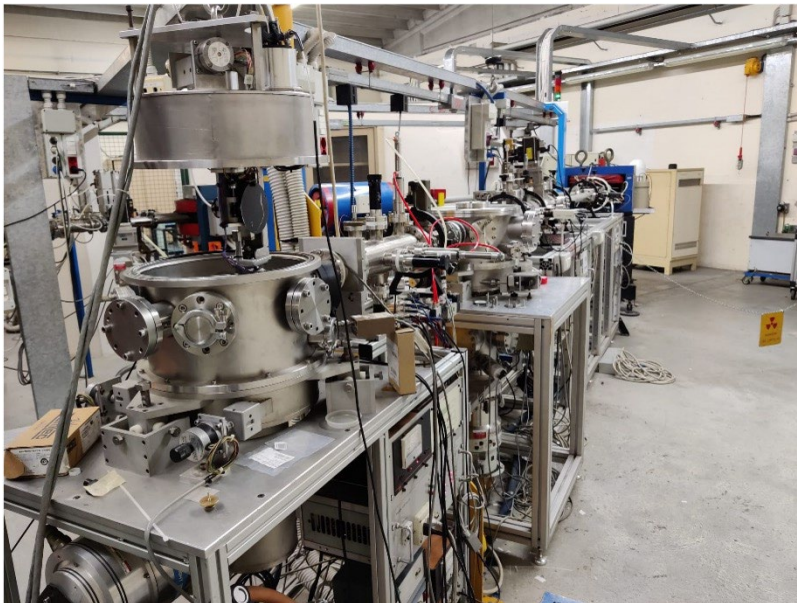
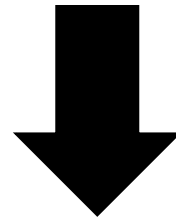
Dichroic filters for photovoltaic applications

Analytical techniques

- Rutherford Backscattering Spectrometry (RBS, ^4He up to 2 MeV)
- Channelling RBS (^4He up to 2 MeV)
- Elastic Recoil Detection Analysis (ERDA ^4He 1.6 MeV)
- Nuclear Reaction Analysis (NRA ^1H 1.6 MeV, 660 keV,)

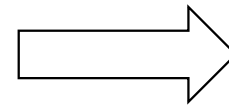


Analysis Chamber



AN2000 - 60° Beam Line

Current
R&D Projects



- **N3G** (CSN 5 INFN)
- **VIRGO** (CSN 2 INFN)
- **OREO** (CSN 5 INFN)
- **BEYOND** (CSN 5 INFN)
- **PLUS** (CNR-IFN Padua)
- **LUNA3** (CSN 3 INFN)
- **GAMMA** (CSN 3 INFN)
- **SPES**
-

N3G - Next Generation Germanium Gamma Detectors

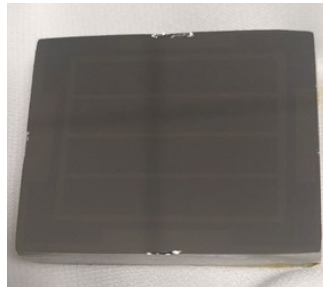
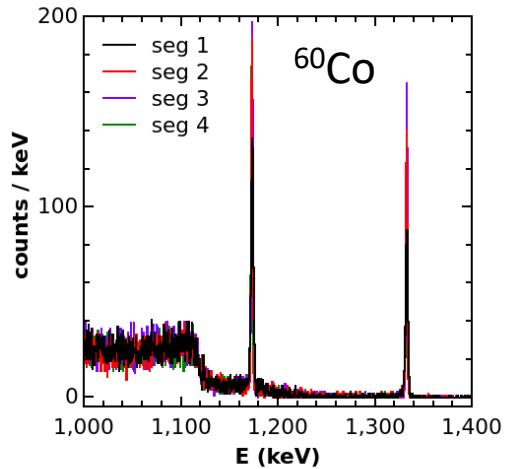
Call of 5th INFN Commission – 2021/2024

PI: Prof. D. De Salvador (UniPD)
Research Units: LNL, PD, FE, MI

AIM

To implement Pulsed Laser Melting technology for the production of complex segmented HPGe coaxial detectors

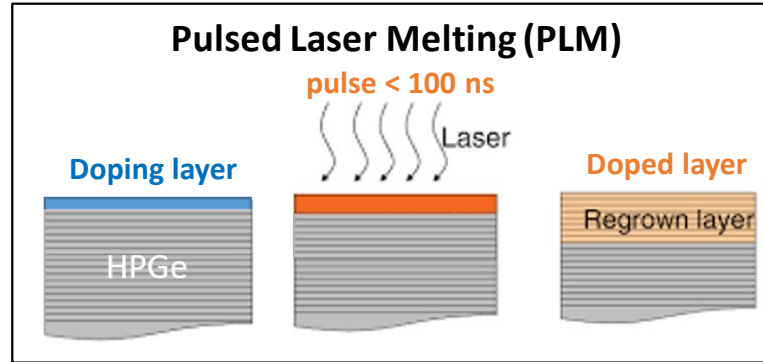
FWHM (1332.50KeV) < 1.8 KeV



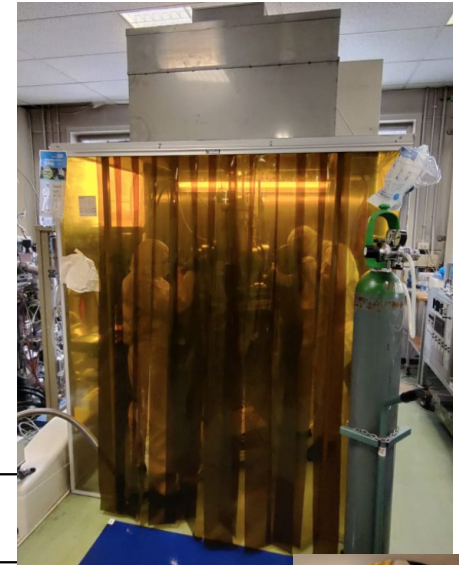
Planar segmented detector



Coaxial segmented detector



Clean sputtering deposition chamber



US 20230170219A1

United States Patent Application Publication (10) Pub. No.: US 2023/0170219 A1
MAGGIONI et al. (43) Pub. Date: Jun. 1, 2023

(54) P+ OR N+ TYPE DOPING PROCESS FOR SEMICONDUCTORS (30) Foreign Application Priority Data
Apr. 22, 2022 (IT) 102020000008662

(71) Applicant: ISTITUTO NAZIONALE DI FISICA NUCLEARE (INFN), Frascati (RM) (IT) (72) Inventors: Gianluigi MAGGIONI, Frascati (RM) (IT); Davide DE SALVADOR, Padova (IT); Daniel Ricardo NAPOLI, Frascati (RM) (IT); Enrico NAPOLITANI, Padova (IT) (51) Int. Cl. H01L 21/225 (2006.01) H01L 21/268 (2006.01) (52) U.S. Cl. CPC H01L 21/2254 (2013.01); H01L 21/268 (2013.01); H01L 31/1808 (2013.01) (57) ABSTRACT
A p+ or n+ type doping process for semiconductors, allows to implement a semiconductor with a highly doped surface layer, and it comprises the steps of: providing a substrate made of semiconductor material; depositing on a surface of 5 the substrate made of semiconductor material a thin source layer made of dopant material acting as dopant source; depositing on said source layer an additional protective surface layer made of semiconductor material; inducing

(21) Appl. No.: 17919,971
(22) PCT Filed: Apr. 20, 2021
(86) PCT No.: PCT/EP2021/060183

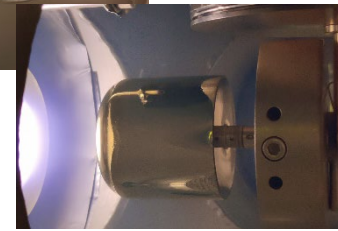
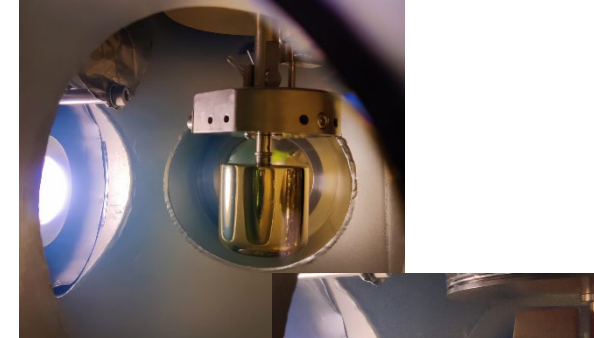
International patent application

N3G - Next Generation Germanium Gamma Detectors

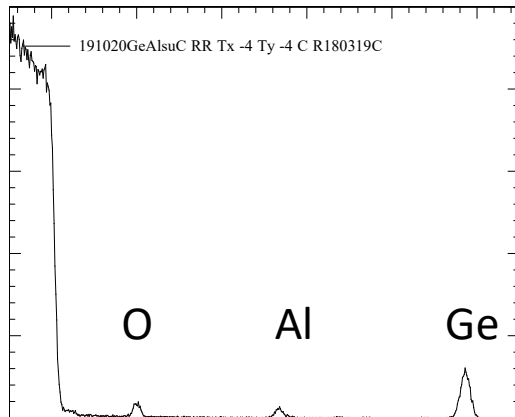
Doping elements: - Al, Ga (p+ dopant), Sb, P, Li (n+ dopant)
[- Ge codeposited or cap layer]

- As-deposited doping layers: characterization of film thickness, composition, presence of contaminants, thickness homogeneity (RBS, channelling RBS, NRA)
- Laser annealed layers: study of the dopant diffusion (RBS, channelling RBS, NRA)

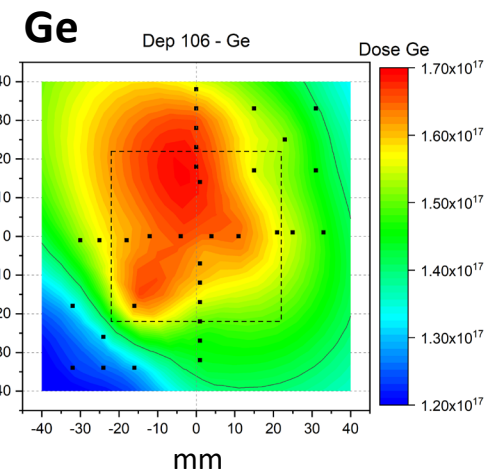
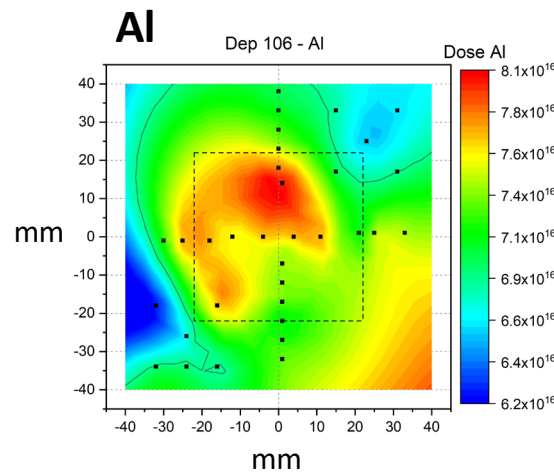
Dopant film
sputter deposition
on coaxial crystal



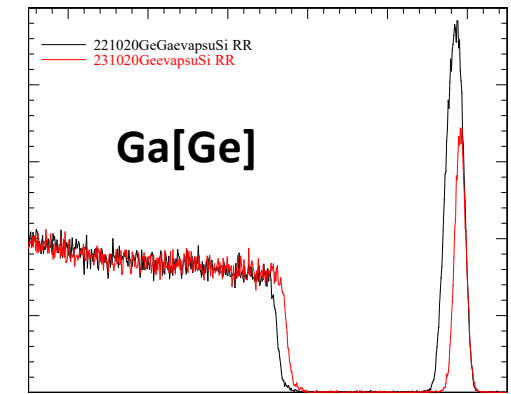
RBS



Film thickness homogeneity



RBS

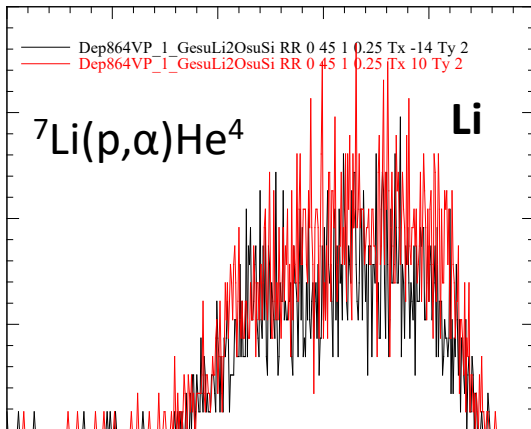


N3G - Next Generation Germanium Gamma Detectors

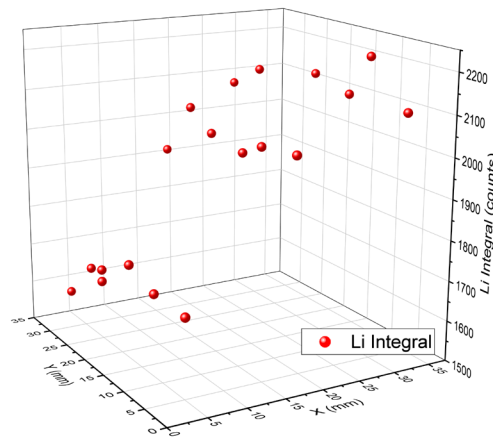
Doping elements: - Al, Ga (p+ dopant), Sb, P, Li (n+ dopant)
[- Ge codeposited or cap layer]

- As-deposited doping layers: characterization of film thickness, composition, presence of contaminants, thickness homogeneity (RBS, channelling RBS, NRA)
- Laser annealed layers: study of the dopant diffusion (RBS, channelling RBS, NRA)

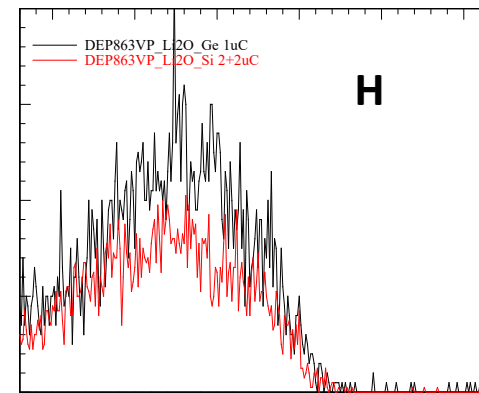
NRA



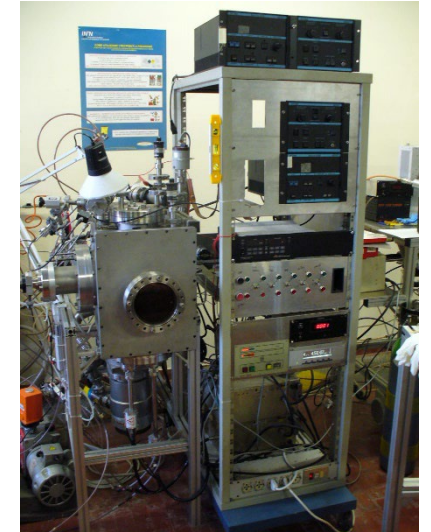
Film thickness homogeneity



ERDA



Sputtering chamber



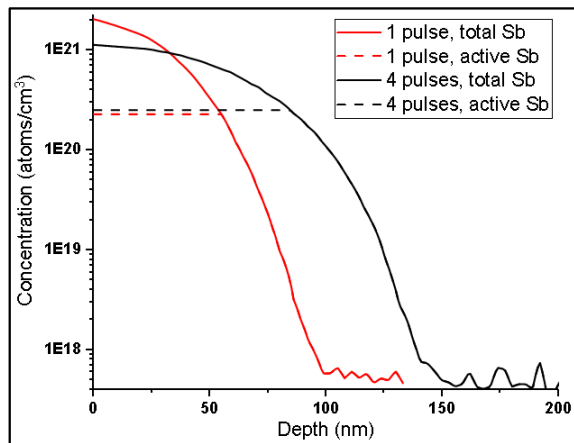
Dopant film
sputter deposition
on coaxial crystal

Doping elements: - Al, Ga (p+ dopant), Sb, P, Li (n+ dopant)
[- Ge codeposited or cap layer]

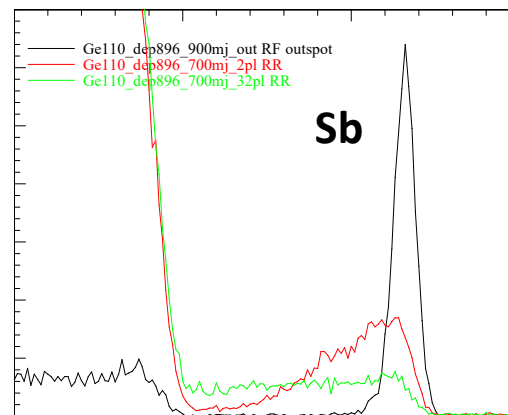
- As-deposited doping layers: characterization of film thickness, composition, presence of contaminants, thickness homogeneity (RBS, channelling RBS, NRA)
- Laser annealed layers: study of the dopant diffusion (RBS, channelling RBS, NRA)



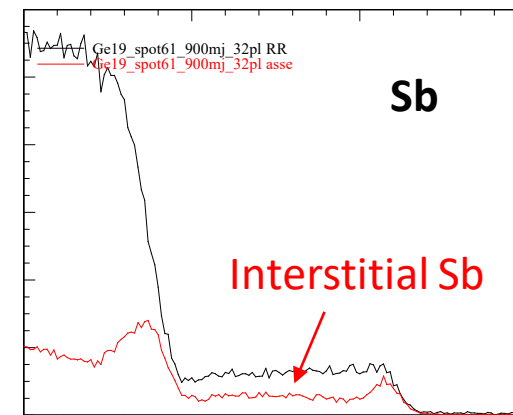
SIMS



RBS



RBS+Channelling RBS



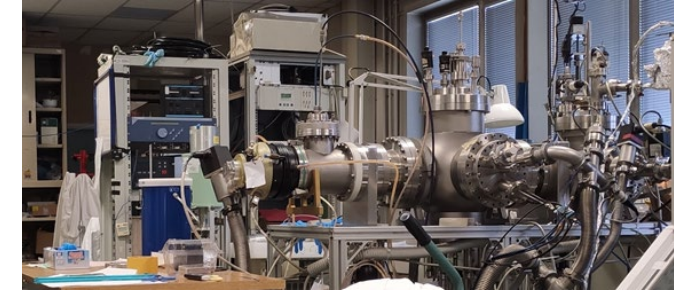
VIRGO

(CSN 2 INFN)

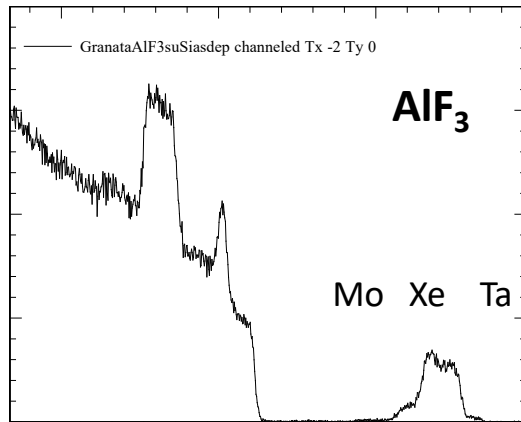
Low Noise mirror coatings for Gravitational Waves (GW) Interferometers

- Deposition and characterization of a-Si and SiC: film thickness, composition, presence of contaminants (RBS, ERDA)
- Characterization of a-Si, AlF₃, SiO₂, Si₃N₄ e TiGe_xO_y films produced in the collaboration: film thickness, composition, presence of contaminants (RBS, channeling RBS, ERDA)

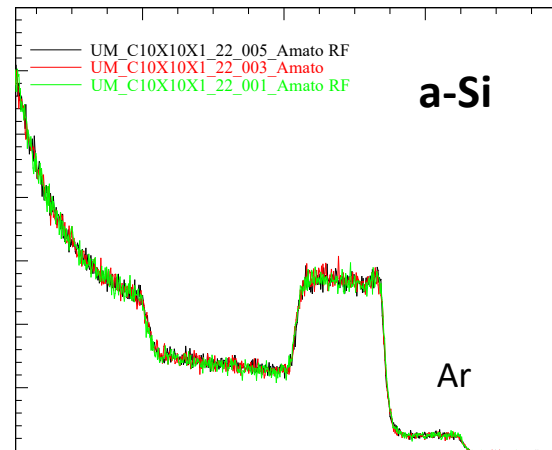
Sputtering chamber ES



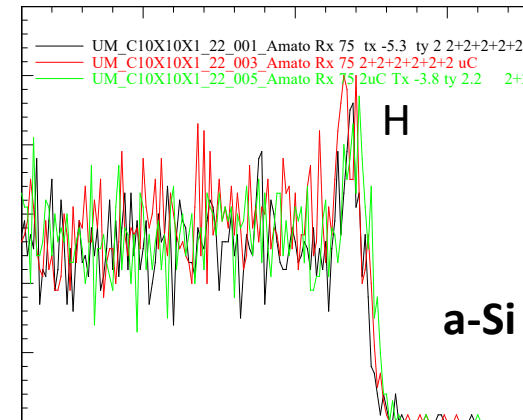
Channelling RBS



RBS



ERDA



SiC-coated sample

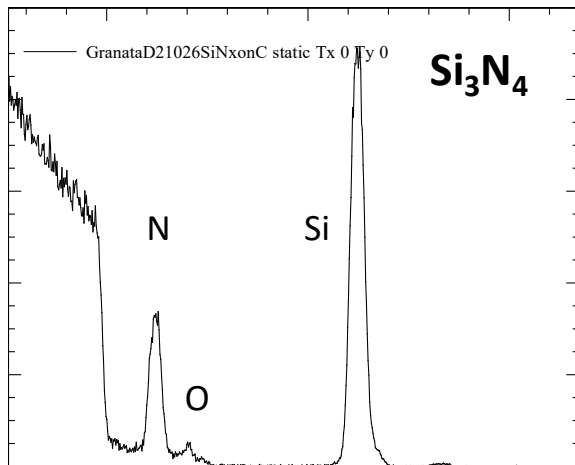
VIRGO

(CSN 2 INFN)

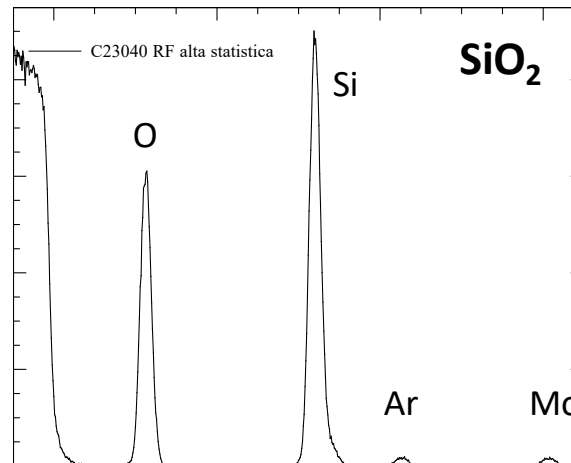
Low Noise mirror coatings for Gravitational Waves (GW) Interferometers

- Deposition and characterization of a-Si and SiC: film thickness, composition, presence of contaminants (RBS, ERDA)
- Characterization of a-Si, AlF₃, SiO₂, Si₃N₄ e TiGe_xO_y films produced in the collaboration: film thickness, composition, presence of contaminants (RBS, channeling RBS, ERDA)

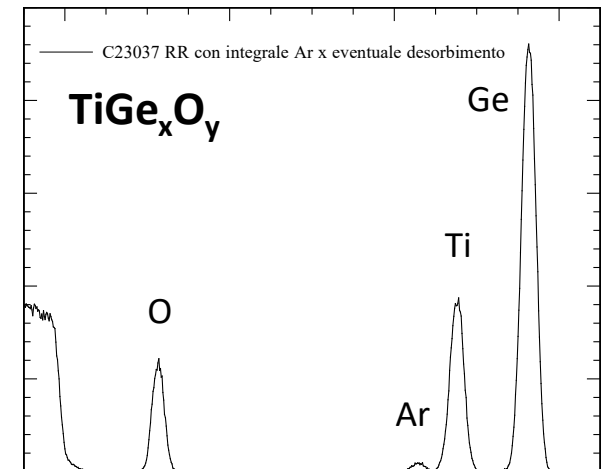
RBS



RBS



RBS



OREO

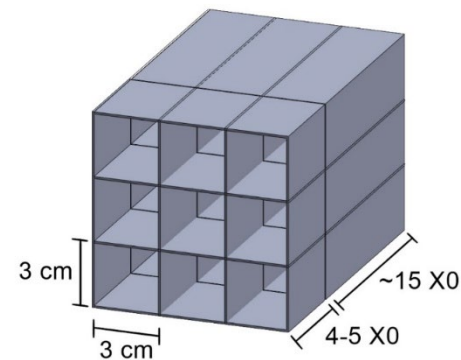
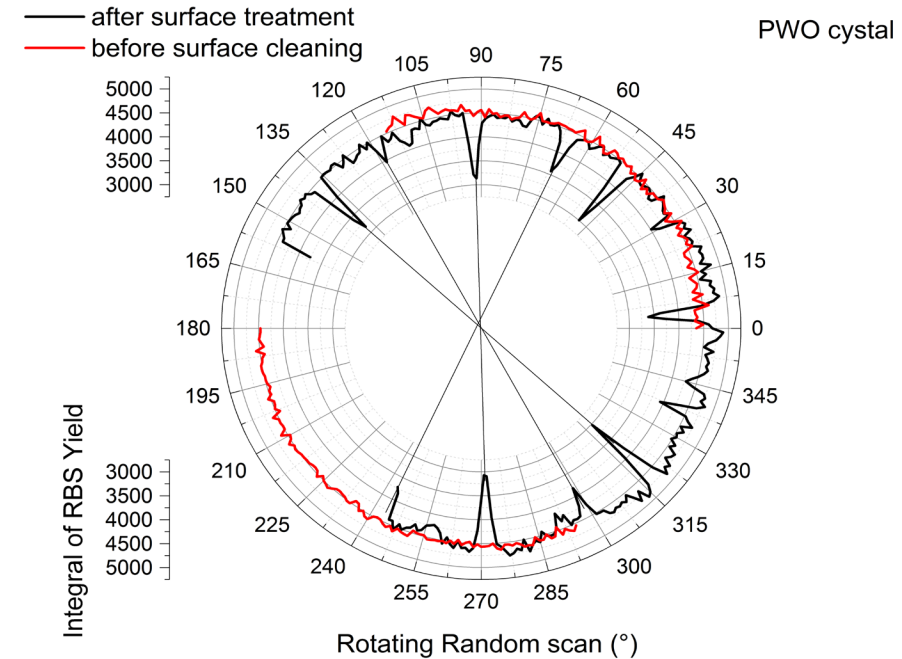
(CSN 5 INFN)

PI: L. Bandiera (FE)

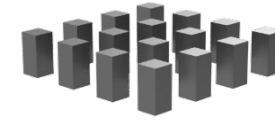
Research Units: Fe, LNL, MIB

Ultra-compact calorimeters for ultra-relativistic particles based on oriented crystals

- **Ultrafast PWO scintillator (PWO-UF*)**: good crystallographic properties; scintillation decay with a time constant of 640 ps at a light yield of 7 phe/MeV and a high radiation tolerance to the electromagnetic component of ionizing radiation. *It is considered a candidate for dual readout of scintillation and Cherenkov photons in electromagnetic calorimetry at future collider.*
- Crystal quality TEST by XRD (FE), **RBS-Channeling (AN & CN) (LNL)**, photoelastic conoscopic method (FE)
- Prototype construction: realization of a 3x3x2 matrix of oriented PWO-UF crystals. Mechanics and precise mounting (FE), SiPM based readout system (MI), **with the development of a technology applicable to large calorimeters;**



BEYOND



PI: Ilaria Fratelli, INFN-BO
Research Units: BO, LNL, PD

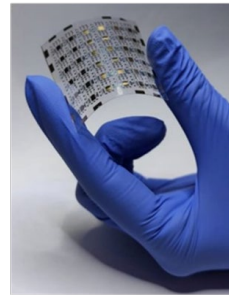
– flexiBLE hYbrid neutrON Detectors –
INFN - Grant Giovani Ricercatori e Ricercatrici

CSN 5 INFN – 2023/24

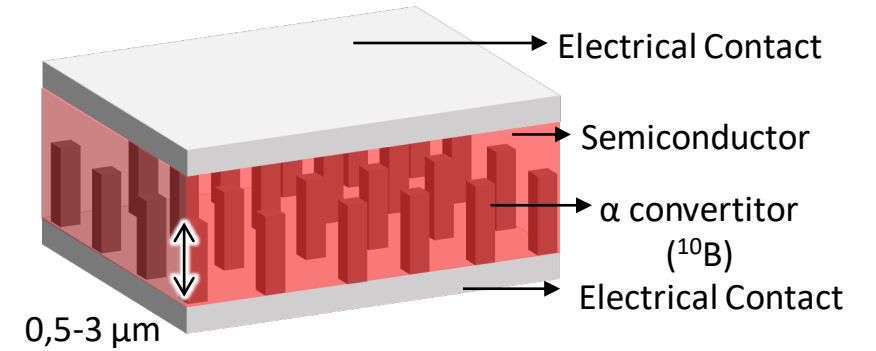
AIM

Realization and characterization of flexible and scalable, large area devices based on perovskite (PVK) and organic materials (OP) for the detection of thermal and fast neutrons

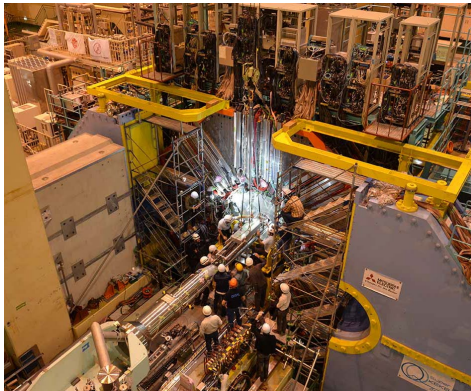
Flexible detectors



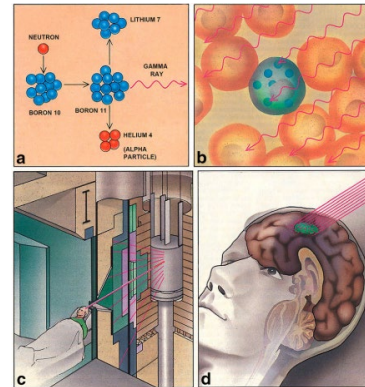
TND THERMAL NEUTRON DETECTION



AMBIENT MONITOR

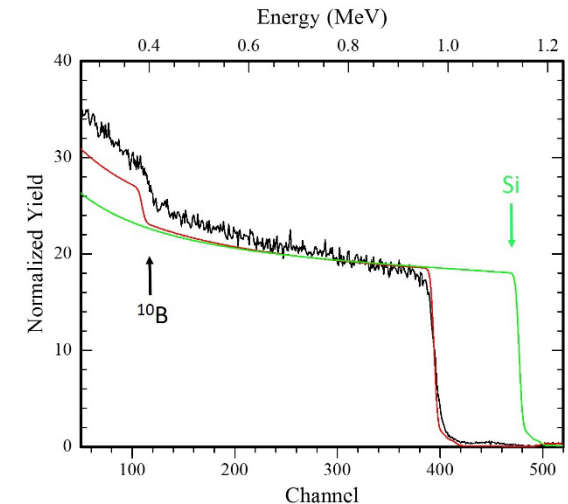


PERSONAL DOSIMETRY



RBS

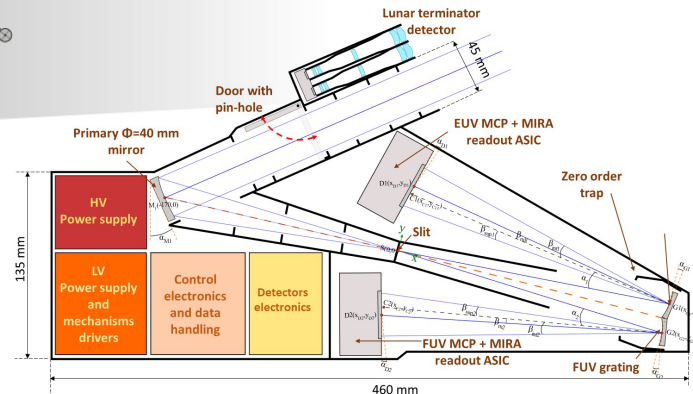
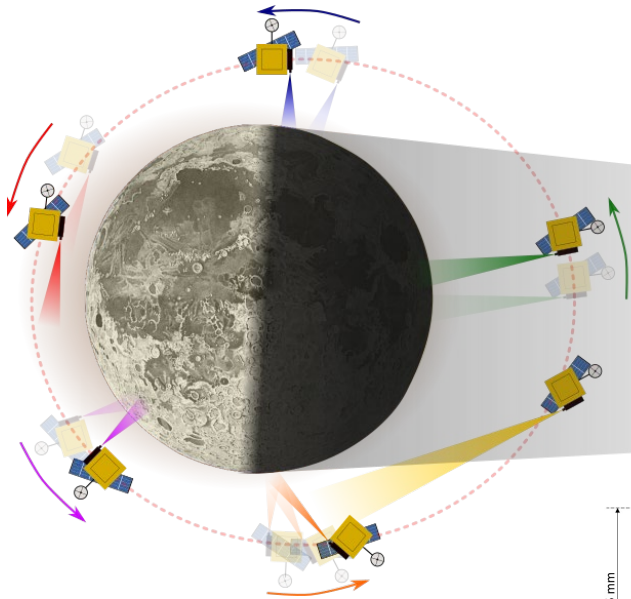
Deposition and characterization of ^{10}B and $^{10}\text{B}_4\text{C}$: film thickness, composition, presence of contaminants (RBS)



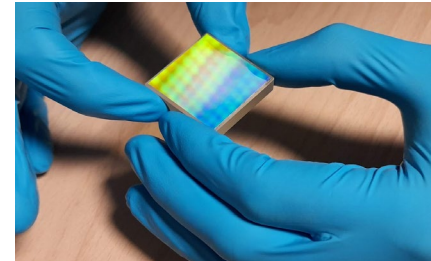
Applications

AIM

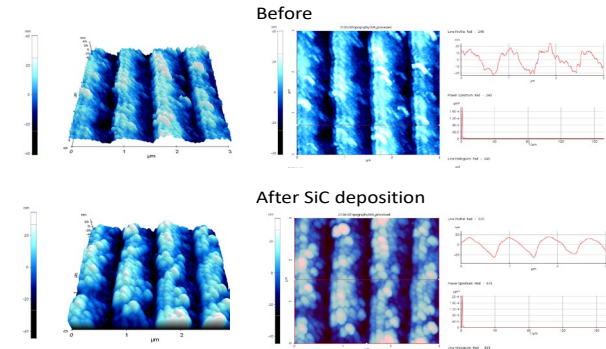
Spectrometer for observations in the far and extreme ultraviolet (FUV/EUV) region to probe the lunar exosphere



UV Grating



SiC thickness: 70 nm (RBS and profilometer).
Grooves density: 1190 lines/mm (AFM)
Average blaze angle: 4.55° (AFM)



OUR CONTRIBUTION
Deposition of SiC_x films on optical gratings to increase their reflectivity

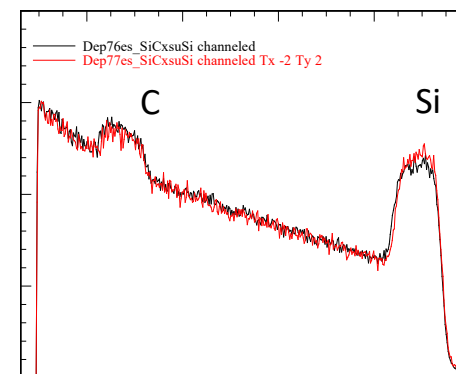
Sputtering chamber ES



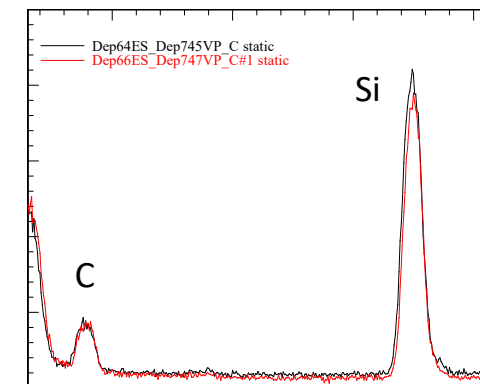
SiC target



RBS



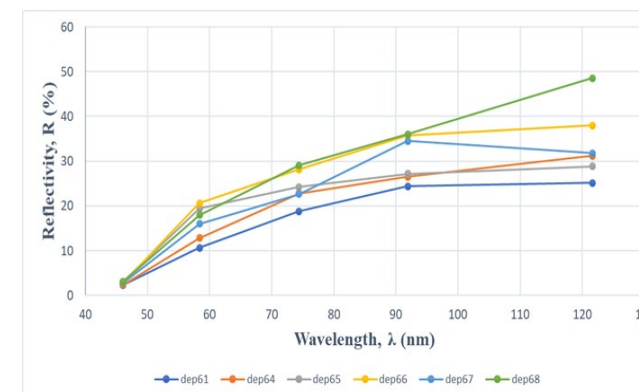
RBS



Film stoichiometry

Deposition nr.	Nr. of Si pieces	Dose Si ($\times 10^{15}$ at/cm ²)	Dose C ($\times 10^{15}$ at/cm ²)	Si/C
56	0			0.74
64	4	297.3	259	1.15
65	3	281	274	1.04
66	2	266.5	255	1.07

UV Reflectance of SiC_x films



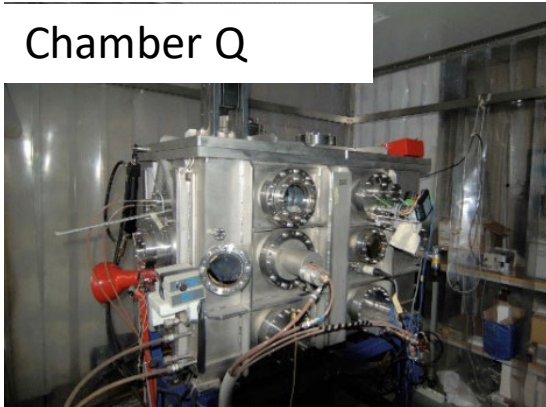
LUNA3 (CSN 3)

PI: G. Imbriani (NA)

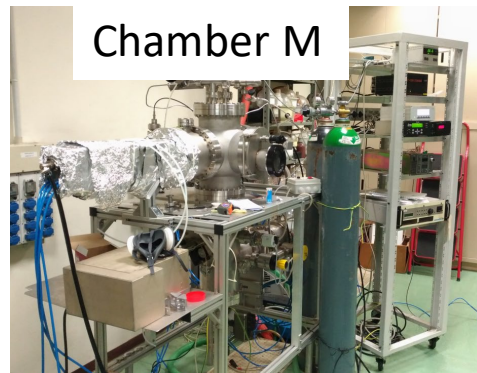
Research Units: BA, GE, LNGS, LNL, MI, NA, PD, ROMA1, TO

- **Nuclear target synthesis (Nitrides, Oxides and Hydride)** with reactive magnetron sputtering technologies using also enriched gasses
- **Engineered thick coating as substrate**, high purity and low contaminants content target substrate development for beam induced background reduction
- **Characterization** of targets and thick coatings by IBA, SEM-EDS, AFM and other techniques

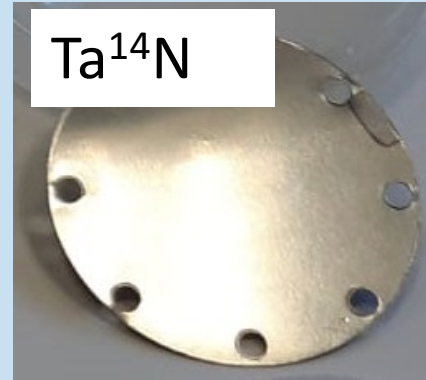
Chamber Q



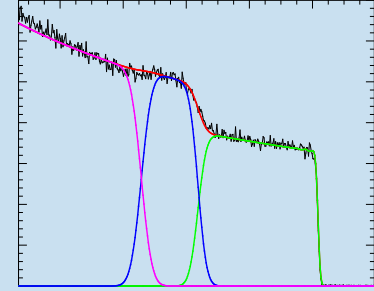
Chamber M



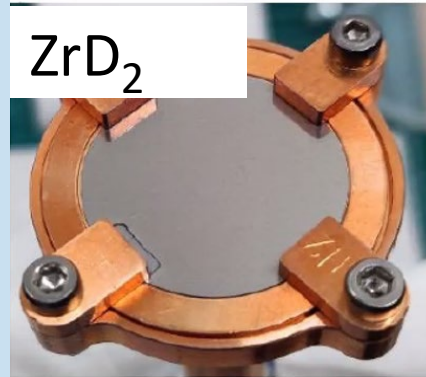
Ta¹⁴N



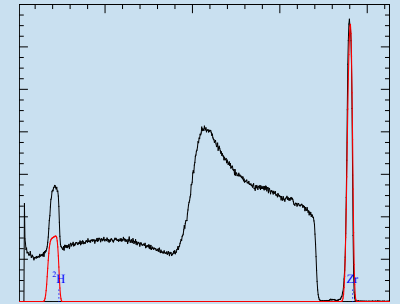
$^{14}\text{N}(p,\gamma)^{15}\text{O}$ experiment, the first shift is ongoing at Bellotti facility (LNGS)



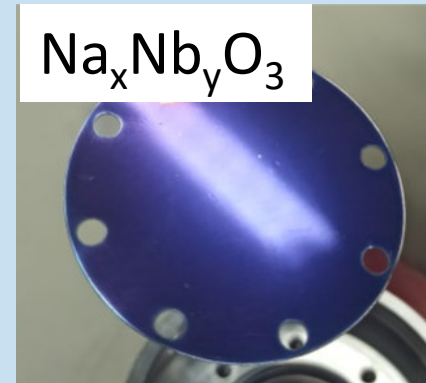
ZrD₂



$2\text{H}(p,\gamma)^3\text{He}$ reaction above 300 keV at Felsenkeller using ZrD₂ targets



Na_xNb_yO₃



Sodium Niobate target deposited on tantalum backing for $^{23}\text{Na}(p,\alpha)^{20}\text{Ne}$ experiment
First test performed at LUNA400 facility (LNGS) in June 2023
Deposition process under investigation

PUBLICATIONS

S. Bertoldo, G. Maggioni, W. Raniero, C. Carraro, S. Riccetto, F. Sgarbossa, D. Scarpa, A. Andrichetto, A. Mazzolari, A. Gadea, D. R. Napoli, E. Napolitani, D. De Salvador, “*New method for the production of thin and stable, segmented n^+ contacts in HPGe detectors*”, **Eur. Phys. J. A** 57 (2021) 177.

M. Granata, D. Forest, A. Amato, G. Cagnoli, M. Bisch, F. Piergiovanni, F. Martelli, M. Montani, G. M. Guidi, M. Bazzan, G. Favaro, G. Maggioni, F. Schiettekatte, M. Chicoine, M. Menotta, A. Di Michele, M. Canepa, “*Optical and mechanical properties of ion-beam-sputtered MgF₂ thin films for gravitational-wave interferometers*”, **Phys. Rev. Applied** 17 (2022) 034058.

G. Favaro, A. Amato, F. Arciprete, M. Bazzan, E. Cesarini, F. De Matteis, T. H. Dao, M. Granata, C. Honrado-Benítez, N. Gutiérrez-Luna, J. I. Larruquert, G. Lorenzin, D. Lumaca, G. Maggioni, M. Magnozzi, E. Placidi, P. Proposito, F. Puosi, “*Measurement and simulation of mechanical and optical properties of sputtered amorphous SiC coatings*”, **Phys. Rev. Applied** 18 (2022) 044030.

M. Bisch, A. Amato, M. Bazzan, G. Cagnoli, M. Canepa, G. Favaro, D. Forest, P. Gobbi, M. Granata, G. M. Guidi, G. Maggioni, F. Martelli, M. Menotta, M. Montani, F. Piergiovanni, L. Valentini, “*Characterization of ion-beam-sputtered AlF₃ thin films for gravitational-wave interferometers*”, **Phys. Rev. Applied** 18 (2022) 054074

E. Di Russo, F. Sgarbossa, P. Ranieri, G. Maggioni, S. Ndiaye, S. Duguay, F. Vurpillot, L. Rigutti, J.-L. Rouviere, V. Morandi, D. De Salvador, E. Napolitani, “*Synthesis of relaxed Ge_{0.9}Sn_{0.1}/Ge by nanosecond pulsed laser melting*”, **Appl. Surf. Sci.** 612 (2023) 155817

S. Ndiaye, S. Duguay, F. Vurpillot, C. Carraro, G. Maggioni, E. Di Russo, D. De Salvador, E. Napolitani, L. Rigutti, “*Atom probe tomography of hyper-doped Ge layers synthesized by Sb in-diffusion by pulsed laser melting*”, **Mater. Sci. Semicon. Processing** 164 (2023) 107641

J. Eberth, H. Hess, P. Reiter, S. Bertoldo, C. Carraro, G. Maggioni, D. R. Napoli, W. Raniero, D. De Salvador, “*Agata detector technology: recent progress and future developments*”, **Eur. Phys. J. A** 59 (2023) 179

THANK YOU!